

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1.-11. (Cancelled)

1 ~~42.~~ (Currently Amended) A scanning exposure method comprising the steps of: moving a mask having first and second patterns, and a substrate in synchronization; and

exposing the first and second patterns on the substrate,
wherein when the first and second patterns are exposed along a synchronous moving direction of the substrate, a part of the first pattern and a part of the second pattern overlap and are exposed, and a synchronous moving speed of the mask and the substrate when there is overlapping exposure is set different from a synchronous moving speed of the same mask and the substrate when there is no overlapping exposure.

2 ~~43.~~ (Currently Amended) The scanning exposure method according to claim ~~42~~, wherein the first pattern and a third pattern adjacent to the first pattern in a direction orthogonal to the synchronous moving direction on the substrate have pluralities of unit patterns arrayed in different predetermined directions, and when the first and third patterns are exposed, the patterns overlap each other in a direction different from the arraying direction of the unit patterns.

3 ~~44.~~ (Currently Amended) A scanning exposure method comprising the steps of: moving a mask having a pattern, and a substrate with respect to a region illuminated with an exposing light, in synchronization; and
exposing the pattern on the substrate,
wherein a size of the illumination region in a direction different from intersecting with a synchronous moving direction of the substrate is synchronously changed

during synchronous movement at the time of exposure in order that a locus of an end of the illumination region on the substrate is extended in a direction different from the synchronous moving direction.

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4 ~~15.~~ (Original) The scanning exposure method according to claim ~~14~~, wherein the size of the illumination region is changed a plurality of times during the synchronous movement.

8 ~~16.~~ (Currently Amended) A scanning exposure system which moves a mask having a pattern, and a substrate, in synchronization, and exposes the pattern on the substrate, comprising:

an illumination region setting device which sets an illumination region of the mask; and

a changing device which synchronously changes a size of the illumination region in a direction different from intersecting with a synchronous moving direction of the substrate during synchronous movement at the time of exposure in order that a locus of an end of the illumination region on the substrate is extended in a direction different from the synchronous moving direction.

9 ~~17.~~ (Currently Amended) A scanning exposure system according to claim 16, which moves a mask having a pattern, and a substrate, in synchronization, and exposes the pattern on the substrate, comprising:

an illumination region setting device which sets an illumination region of the mask; and

a changing device which changes a size of the illumination region in a direction different from a synchronous moving direction of the substrate during synchronous movement.

wherein the illumination region setting device includes a pair of blind plates which respectively have openings with a predetermined width in the synchronous moving direction and are movable in a direction that is different from the synchronous moving direction.

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10. (Currently Amended) A scanning exposure system according to claim 16, wherein the illumination region has a pentagonal or hexagonal shape.

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11. (Currently Amended) A scanning exposure system according to claim 16, wherein the illumination region setting device provides the illumination region which has triangular ends.

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12. (Currently Amended) A scanning exposure system according to claim 19, which moves a mask having a pattern, and a substrate, in synchronization, and exposes the pattern on the substrate, comprising:

an illumination region setting device which sets an illumination region of the mask; and

a changing device which changes a size of the illumination region in a direction different from a synchronous moving direction of the substrate during synchronous movement,

wherein the ends of the illumination region are exposed to an illumination gradient.

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21. (Currently Amended) A scanning exposure system according to claim 16, which moves a mask having a pattern, and a substrate, in synchronization, and exposes the pattern on the substrate, comprising:

an illumination region setting device which sets an illumination region of the mask; and

a changing device which changes a size of the illumination region in a direction different from a synchronous moving direction of the substrate during synchronous movement.

wherein the illumination region setting device includes at least one blind plate for providing the illumination region with a triangular end and at least one end light-shielding blind plate which covers the triangular end of the at least one illumination region. 3

5 ~~22~~ (Previously Added) A scanning exposure method according to claim ~~14~~, wherein the illumination region has a pentagonal or hexagonal shape. 3

6 ~~23~~ (Currently Amended) A scanning exposure method according to claim ~~14~~, wherein the size, of the illumination region, in a direction different from intersecting with the synchronous moving direction of the substrate is continuously changed by reversing a direction of illumination during the synchronous movement. 3

24 ~~7~~ (Currently Amended) A scanning exposure method according to claim ~~14~~, wherein an adjacent pattern is exposed so as to be partially overlapped with the pattern of the mask which was formed on the substrate. 3

25 ~~16~~ (Currently Amended) A scanning exposure method according to claim ~~24~~, comprising the steps of:

moving a mask having a pattern, and a substrate, with respect to a region illuminated with an exposing light, in synchronization; and exposing the pattern on the substrate,

wherein a size of the illumination region in a direction intersecting with a synchronous moving direction of the substrate is synchronously changed during synchronous movement, and wherein an overlapping part which is partially overlapped with the pattern is formed in a zigzag pattern. 3

17 ~~26.~~ (Currently Amended) A scanning exposure method according to claim ~~24~~²⁵,¹⁶ wherein the adjacent pattern, which is adjacent to the pattern in an orthogonal direction to the synchronous moving direction, is exposed so as to be partially overlapped with the pattern of the mask which was formed on the substrate.

18 ~~27.~~ (Currently Amended) A scanning exposure method according to claim ~~24~~²⁵,¹⁶ wherein the adjacent pattern, which is adjacent to the pattern in the synchronous moving direction, is exposed so as to be partially overlapped with the pattern of the mask which was formed on the substrate.

19 ~~28.~~ (Currently Amended) A scanning exposure method according to claim ~~23~~, wherein a width of an overlapping part which is partially overlapped with the pattern in the synchronous moving direction is substantially equal to that of the illumination region in the synchronous moving direction *17* ~~26~~, wherein the adjacent pattern which is adjacent to the pattern in the synchronous moving direction is exposed so as to be partially overlapped with the pattern of the mask which was formed on the substrate.

29. ¹³ (New) A scanning exposure system according to claim ~~20~~, further comprising an alignment member which performs alignment between the mask and the substrate to partially overlap a part of the pattern of the mask with a part of the pattern which was exposed on the substrate.

30. ¹⁴ (New) A scanning exposure system according to claim ~~29~~, wherein a synthesized pattern is formed by exposing a plurality of the patterns of the mask in a manner so as to partially overlap the plurality of the patterns.

20 ^{31.} (New) A scanning exposure method comprising the steps of:
moving a mask having a pattern, and a substrate, with respect to an illumination region that is illuminated with an exposing light, in synchronization; and
exposing the pattern on the substrate,

wherein the illumination region is moved in a direction intersecting with a synchronous moving direction of the substrate during synchronous movement at the time of exposure:

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32. ²¹ (New) A scanning exposure method according to claim ²⁰ 31, wherein a size of the illumination region in the direction intersecting with the synchronous moving direction of the substrate is continuously changed during the synchronous movement.